

Contacting Nanowires

Progress Report

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22-11-2006

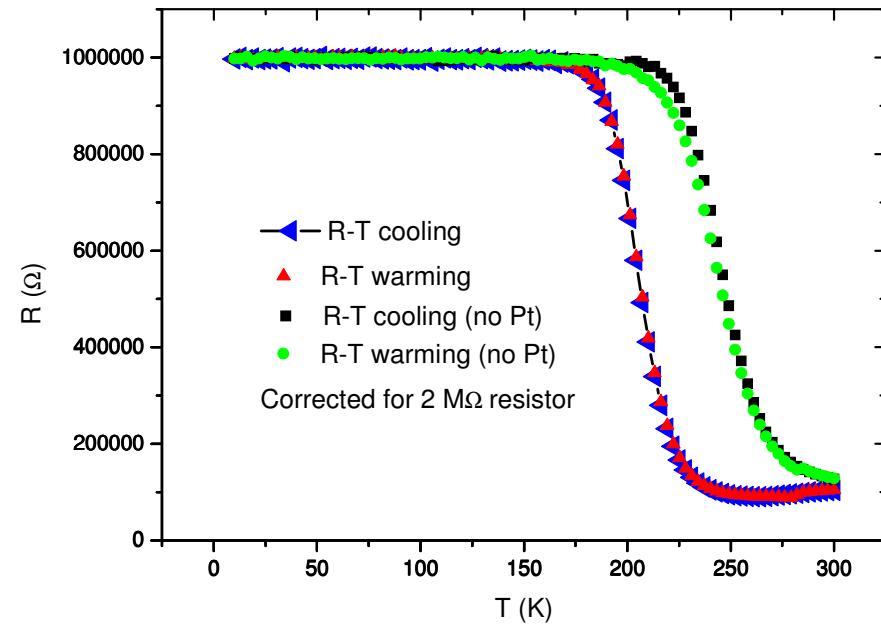
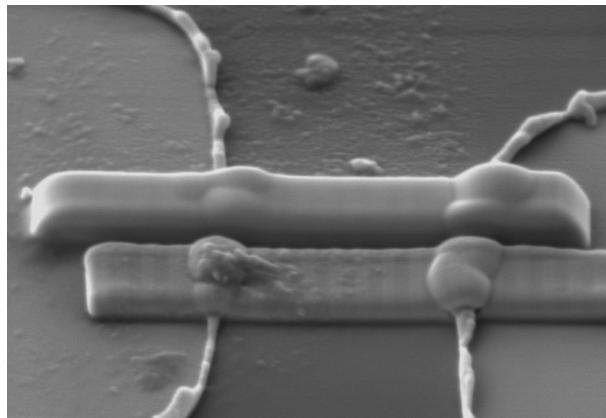
Outline

- Before: EBID vs. EBPG
- Results: sputtering
- Recent results: evaporation

Quick Reminder

Why EBPG and not EBID?

Strip: $t = 500 \text{ nm}$
 $w = 800 \text{ nm}$
 $l = 6.5 \mu\text{m}$

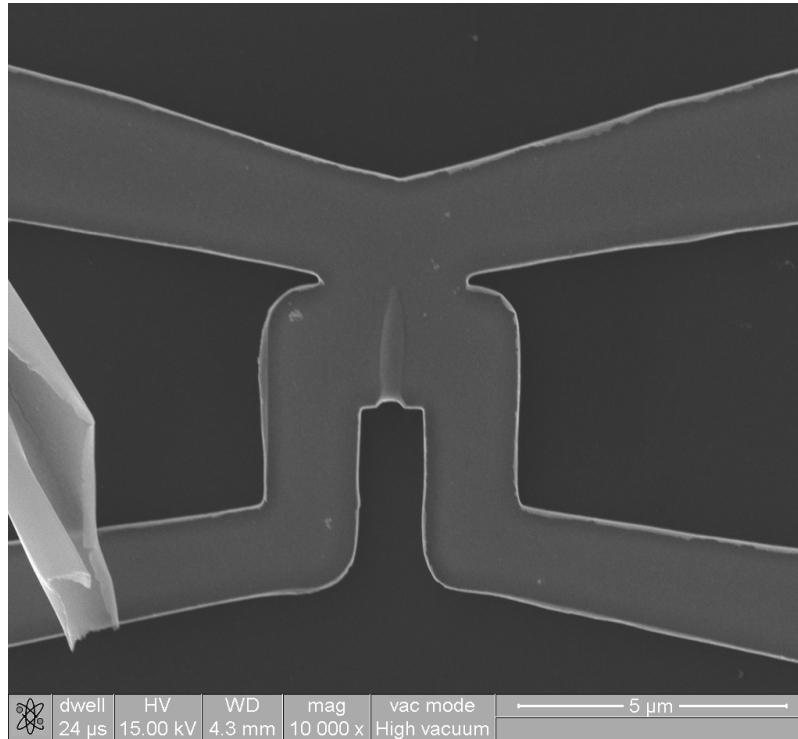
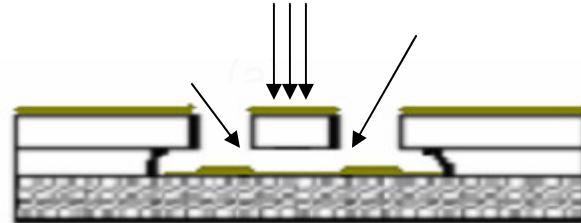


Low Pt concentration!

Use lift-off

Results: Sputtering

Resist: bilayer PMMA-PMGI



Area Dose: $160 \mu\text{As}/\text{cm}^2$

$I = 50 \text{ pA}$

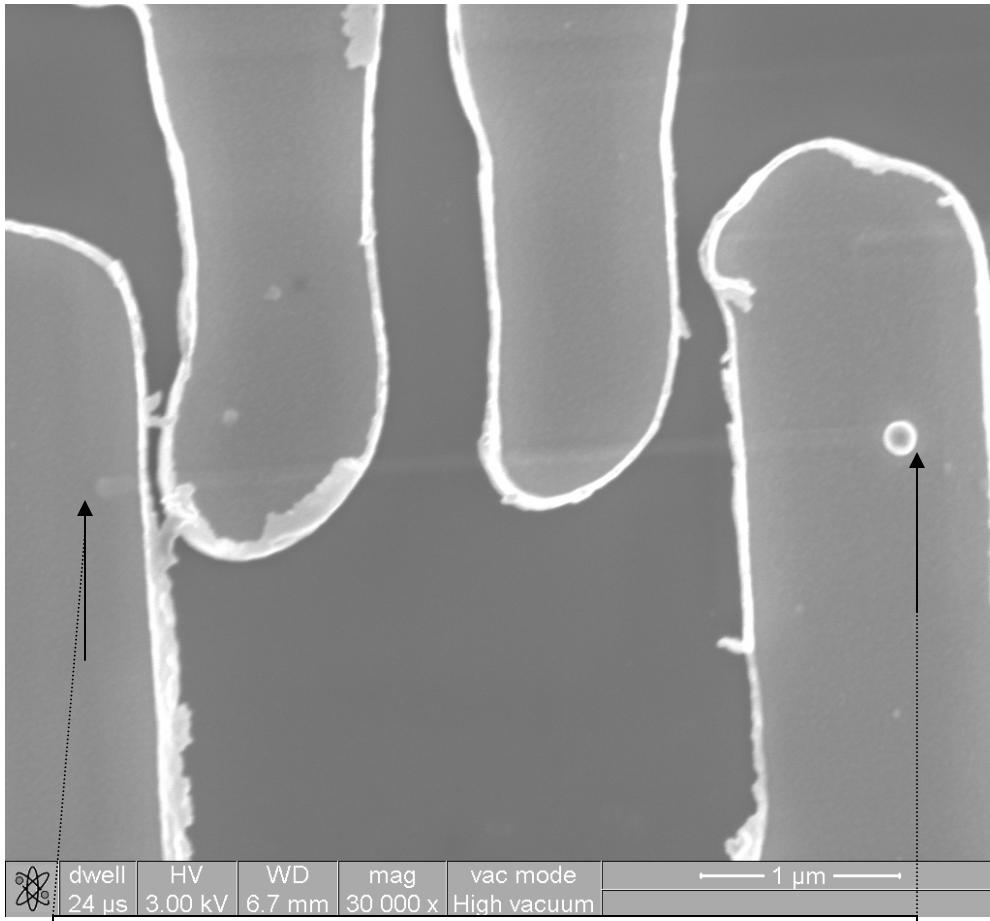
Dose factor: 2.3

Nominal sizes:

strip: 400 nm

spacing: 500 nm

Results: sputtering



Resist: bilayer PMMA-MMA

Area Dose: $80 \mu\text{As}/\text{cm}^2$

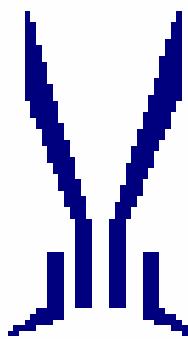
$I = 50 \text{ pA}$

Dose factor: 1.5

“Ears”

Dose test: evaporation

Resist: single layer PMMA!!



Nominal sizes:

strip: 200 nm

spacing: 400 nm

Area Dose: 80 $\mu\text{As}/\text{cm}^2$

$I = 50 \text{ pA}$

Dose factor: 1.0 \rightarrow 5.9

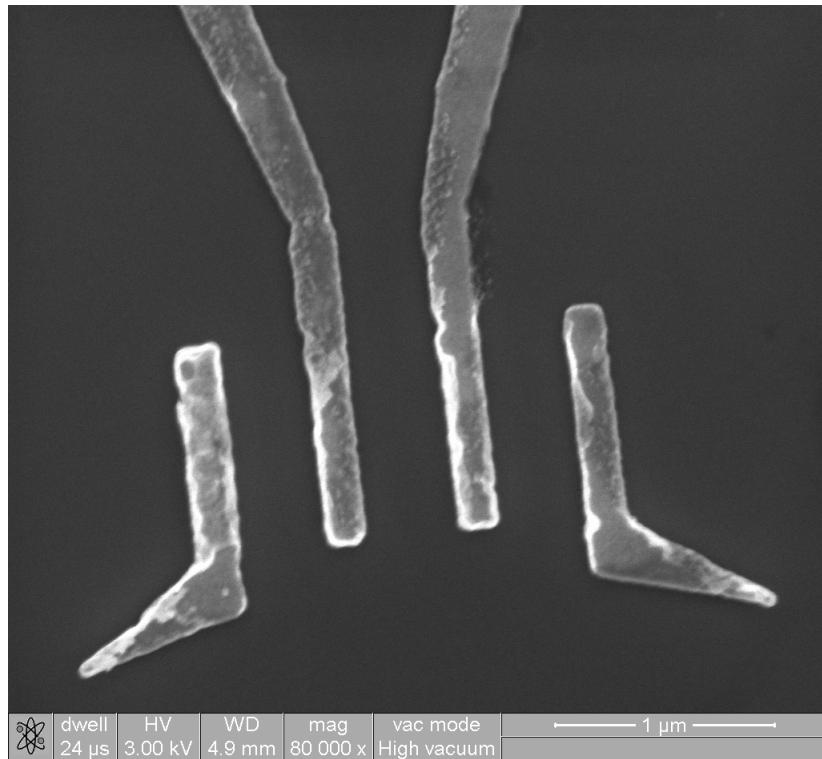
Results evaporation

Dose factor: 1.3

Sizes:

strip: 175 nm

spacing: 415 nm

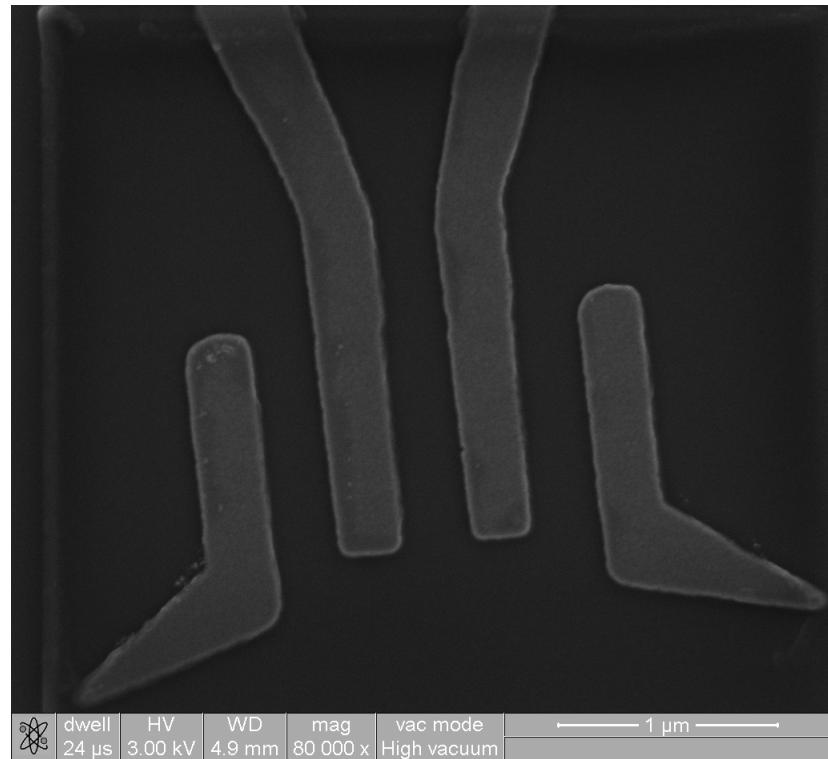


Dose factor: 5.9

Sizes:

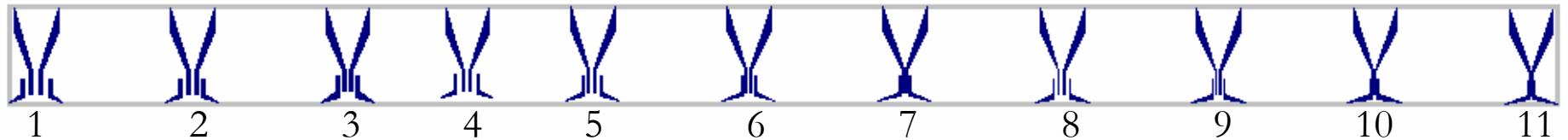
strip: 310 nm

spacing: 300 nm



Dose test: evaporation

Resist: single layer PMMA!!



	Strip (nm):	Spacing (nm):
1	200	400
2	200	300
3	200	200
4	100	400
5	100	300
6	100	200
7	100	100
8	50	300
9	50	200
10	50	100
11	50	50

Area Dose: $80 \mu\text{As}/\text{cm}^2$

$I = 50 \text{ pA}$

Dose factor: $1.3 \rightarrow 4.1$

Results: evaporation

Dose factor: 1.6

Sizes:

strip: 375 – 395 nm

spacing: 95 nm



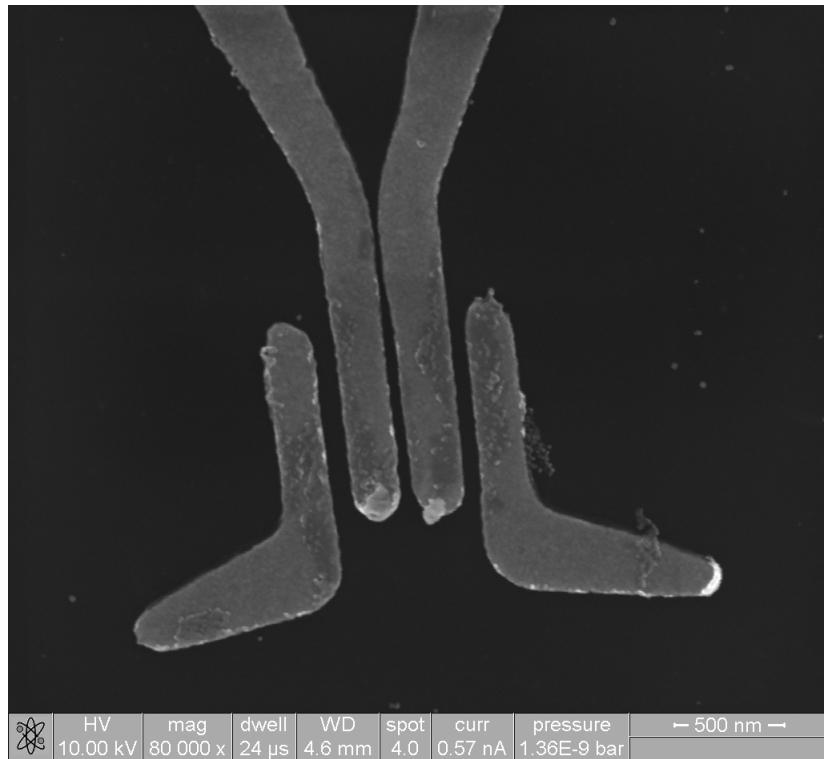
Results: evaporation

Dose factor: 2.1

Sizes:

strip: 220 nm

spacing: 98 - 25 nm

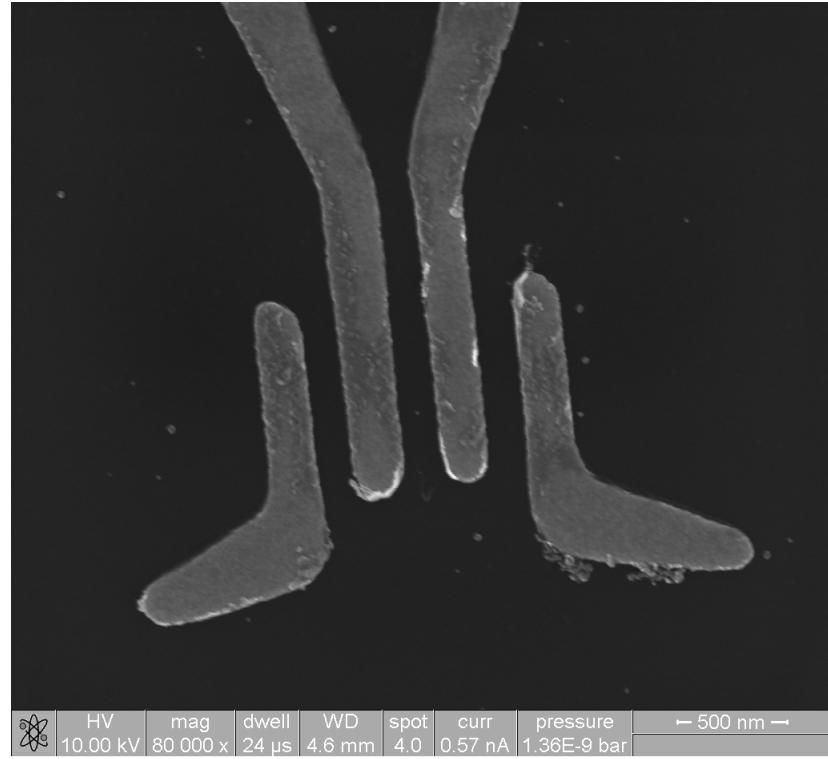


Dose factor: 2.1

Sizes:

strip: 220 nm

spacing: 157 nm



Total width: 1.39 µm

Conclusions

- Sputtering: nanowire longer than 3 - 4 μm !
- Evaporation: no ears, clean lift with single layer PMMA
- Minimum nanowire length: 1.39 μm !